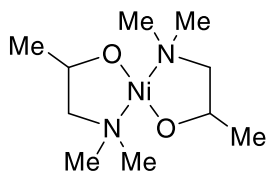


Catalog # 28-0025 Bis[1-(N,N-dimethylamino)-2-propanolato]nickel(II), 99% NiDMAP



Thermal Behavior:

- Sublimation at 100°C

Technical Notes:

1. ALD precursor for nickel thin film and nanoparticle deposition

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
Ni	ALD	100°C	1-5 Torr	H ₂	300°C	1

References:

1. [Electrochimica Acta 2018, 284, 211](#)